ABSTRACT

In a reticle substrate is used for forming a reticle held on a stepper and has main surfaces opposing each other, side faces, and chamfered surfaces formed between main surfaces and side faces, a flatness-measuring area is defined as an area excluding a peripheral area of a width of 3 mm inwardly laid from a boundary between the main surface and the chamfered surfaces and has a flatness of 0.5 μm or less, and a maximum height from a reference plane falls between -1 and 0 μm at the boundary between the main surface and the chamfered surface